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APR 10 2006 09 DEC 2005

PATENT

SHIGA7.037APC

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

|                |   |   |
|----------------|---|---|
| Applicant      | : | TAMURA, K. et al.   |
| Appl. No.      | : | Unknown   |
| Filed          | : | Herewith  |
| For            | : | POSITIVE RESIST<br>COMPOSITION, RESIST<br>LAMINATES AND PROCESS<br>FOR FORMING RESIST<br>PATTERNS |
| Examiner       | : | Unkown  |
| Group Art Unit | : | Unknown   |

PRELIMINARY AMENDMENT

**Mail Stop Amendment**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 3 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.